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Filing Date October 9, 2003

Group Art Unit 2811

Examiner Name Unknown

Confirmation No. 1986

Attorney Docket No. 400.257US01

# GENERAL TRANSMITTAL FORM UNDER 37 CFR 1.8

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(LARGE ENTITY)

Title: FULLY DEPLETED SILICON-ON-INSULATOR CMOS LOGIC

Mail Stop Amendment Commissioner for Patents P. O. Box 1450 Alexandria, VA 22313-1450

#### **Enclosures**

### The following documents are enclosed:

- X Information Disclosure Statement (1 pg.); Form 1449 (7 pgs.); 58 copies of cited references; U.S. reference(s) not included pursuant to 37 C.F.R. 1.98 (c)(2)(i);
- X An itemized return-receipt postcard

Leffert Jay & Polglaze, P.A. P.O. Box 581009 Minneapolis, MN 55458-1009 T - 612/312-2200 F - 612/312-2250

## Please charge any additional fees or credit any overpayments to Deposit Account No. 501373.

### **CUSTOMER NO. 27073**

Submitted By						
Name	Kenneth W. Bolvin R	eg. No. 34,	125	Telephone	(612) 312-2211	
Signature	ignature Genneth W. Bolvi Date 5/24/09					
Certificate of Mailing						
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Amendment, Commissioner for Patents, P. O. Box 1450, Alexandria, VA) 22313-1450 on May 24, 2004.						
Name	Rhonda L. Foley	Signature	-Kh	mæl	tolen	

(LARGE ENTITY TRANSMITTAL UNDER 37 CFR § 1.8)

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•	First Named Inventor	Leonard Forbes	1)
RÁ	Sarial No.	10/682,590	INFORMATION
-	Filing Date	October 9, 2003	DISCLOSURE
	Group Art Unit	2811	STATEMENT
	Examiner Name	Unknown	
	Confirmation No.	1986	
	Attorney Docket No.	400.257US01	
	Title: FULLY DEPLET	ED SILICON-ON-INSULA	TOR CMOS LOGIC

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In compliance with 37 C.F.R. §§ 1.56 and 1.97, et seq., the enclosed materials are brought to the attention of the Examiner for consideration in connection with the above-identified Application. Pursuant to 37 C.F.R. 1.98 (a)(2)(i), as this application was filed after June 30, 2003, Applicant has not included copies of U.S. Patents or U.S. Patent Applications. Applicant respectfully requests that this Information Disclosure Statement be entered and the references listed on the attached Form 1449 be considered by the Examiner and made of record. Pursuant to MPEP §609, Applicant further requests that the Examiner initial next to each reference on the Form 1449 to indicate that the listed references have been considered. Applicant further requests that a copy of the initialed Form 1449 be returned with the next official communication.

As an Office Action has not yet issued in this application, Applicant believes that no fees are due. However, the Commissioner for Patents is hereby authorized to charge any additional fees to Deposit Account No. 501373. If the Examiner has any questions or concerns regarding this application, please contact the undersigned at (612) 312-2211.

Respectfully submitted,

Date:

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### INFORMATION DISCLOSURE STATEMENT FORM PTO-1449

Title: FULLY DEPLETED SILICON-ON-

**INSULATOR CMOS LOGIC** 

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